

DCD gain, g_m and g_q measurement of PXD modules

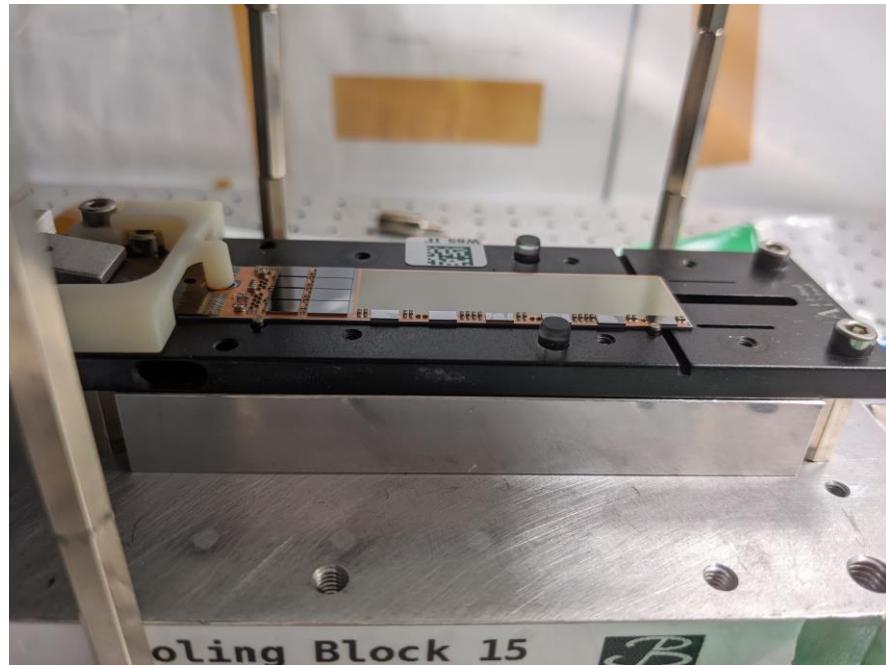
24th International DEPFET workshop

Master Thesis by Larissa von Jasienicki
Talk by Munira Khan on behalf of the Bonn group



CALIBRATION OF PXD MODULES

- 12 module testing steps to check functionality and characterize modules
- Homogeneous efficient pixel response
 - Tuning of matrix biasing voltages
 - Tuning of DCD voltages and parameters
- All studies presented here are on fully optimized modules

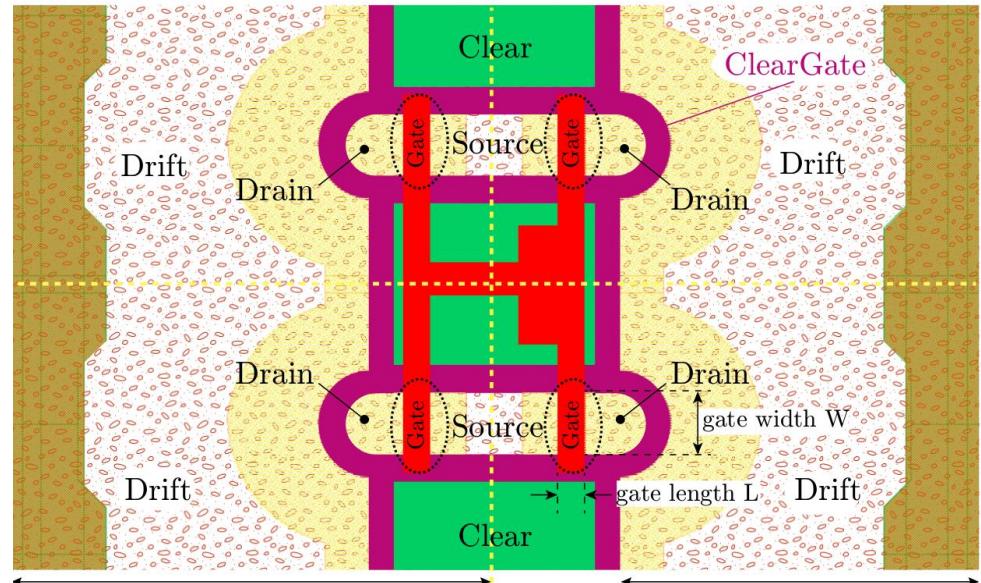


PXD Module Characterization

Biassing voltage studies

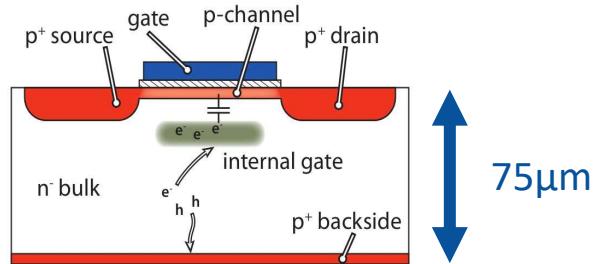
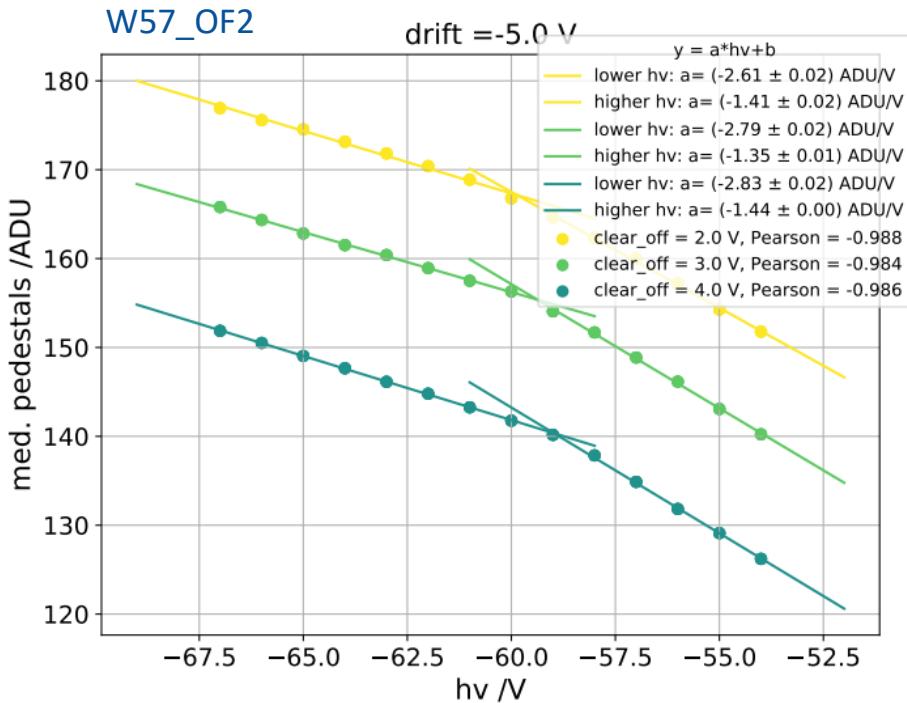
BIASING VOLTAGE STUDIES

- Impact of different biasing voltages on pedestals
- Biasing voltages:
 1. $h\nu$: backside
 2. drift voltage: drift implants
 3. clear-off voltage: clear contact



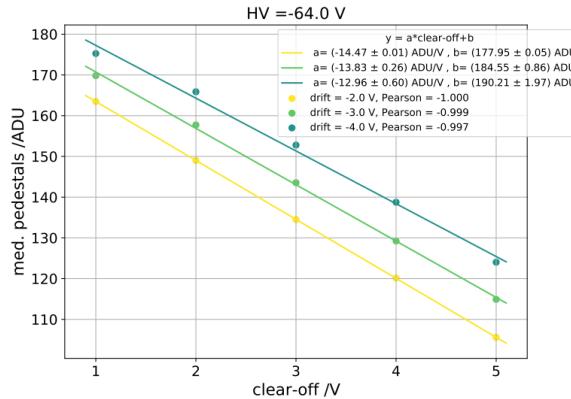
Müller Felix (2017): Characterization and optimization of the prototype DEPFET modules for the Belle II Pixel Vertex Detector.

IMPACT OF HV

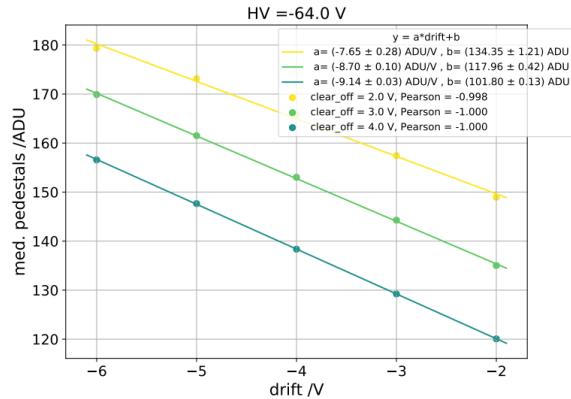


- hv influences pedestals!
- Acts as remote gate ($\sim 75\mu\text{m}$)
- Coupling to FET
- Change of potential influences drain current
- hv > -60V: not fully depleted

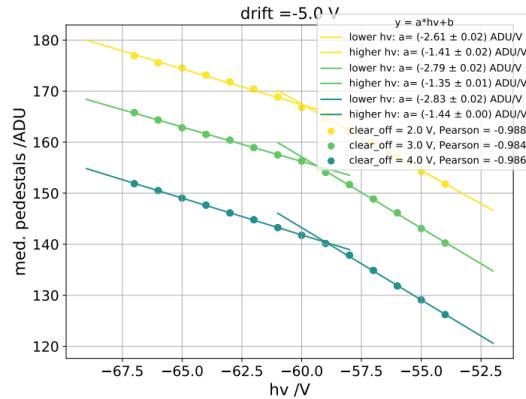
IMPACT BIASING VOLTAGES



-13.7 ADU/V

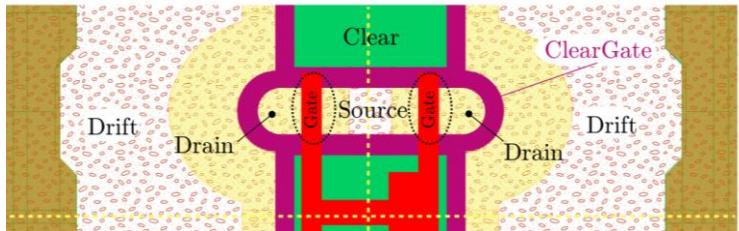


-8.5 ADU/V



-1.9 ADU/V

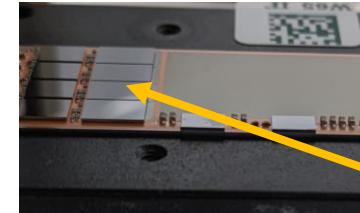
- Couplings to FET
- Clear-off voltage has highest impact on FET



Tuning of DCD parameters

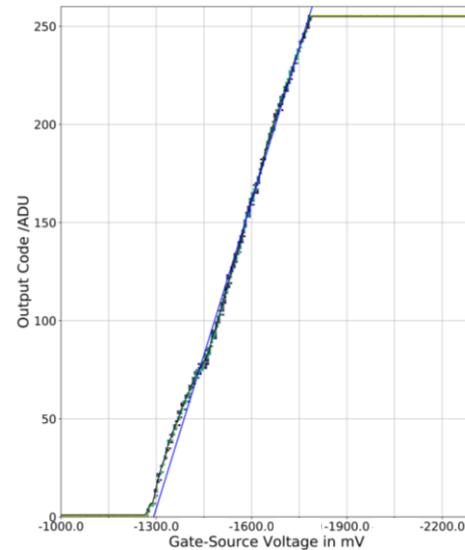
Measurements of g_m and g_q

TUNING DCD PARAMETER

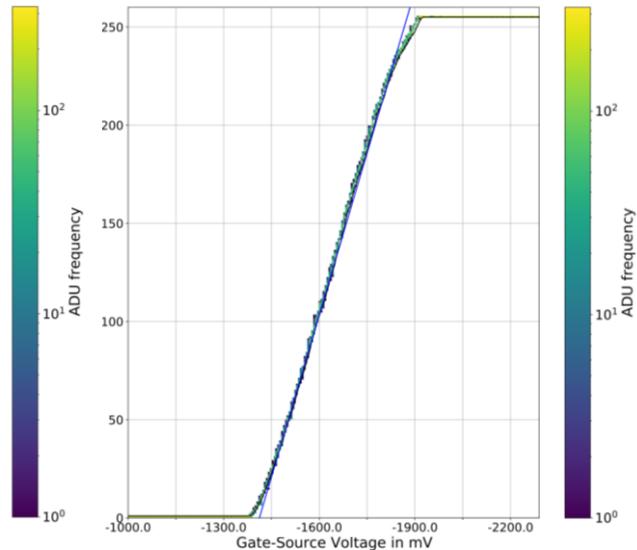


DCDs

- 256 ADC (Analog to Digital Converter) channels per chip
- Optimize ADC response:
 - Tune voltages and settings
 - Whole dynamical range
 - No missing codes
 - As linear as possible
- No DCD gain in units of current



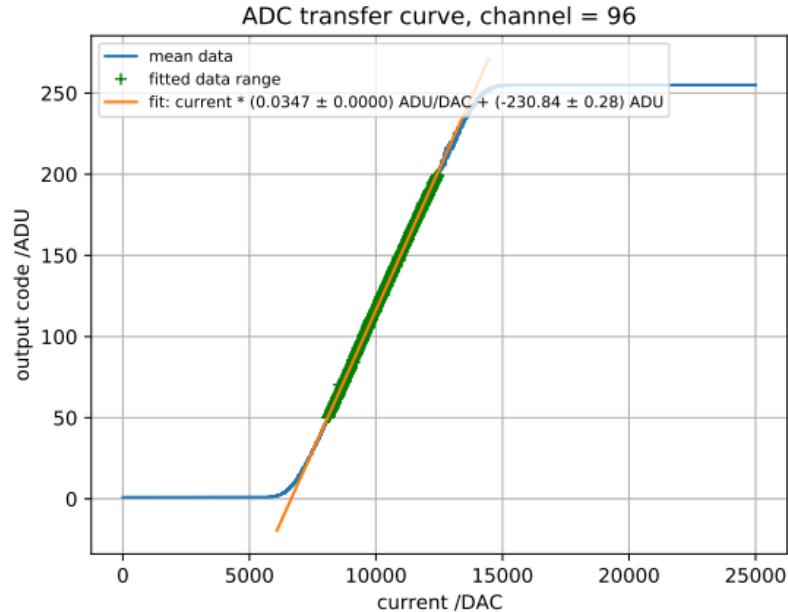
Bad setting



Good setting

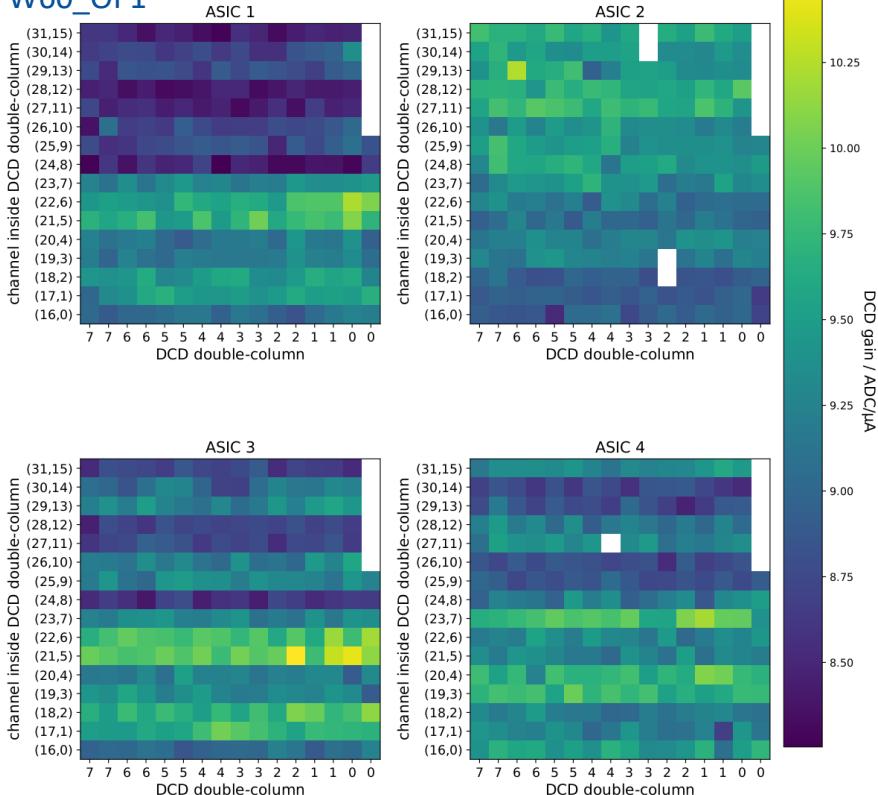
DCD GAIN MEASUREMENT

- Exact channel-by-channel calibration through injection of external current
- Necessary to evaluate DEPFET parameters, such as g_m and g_q



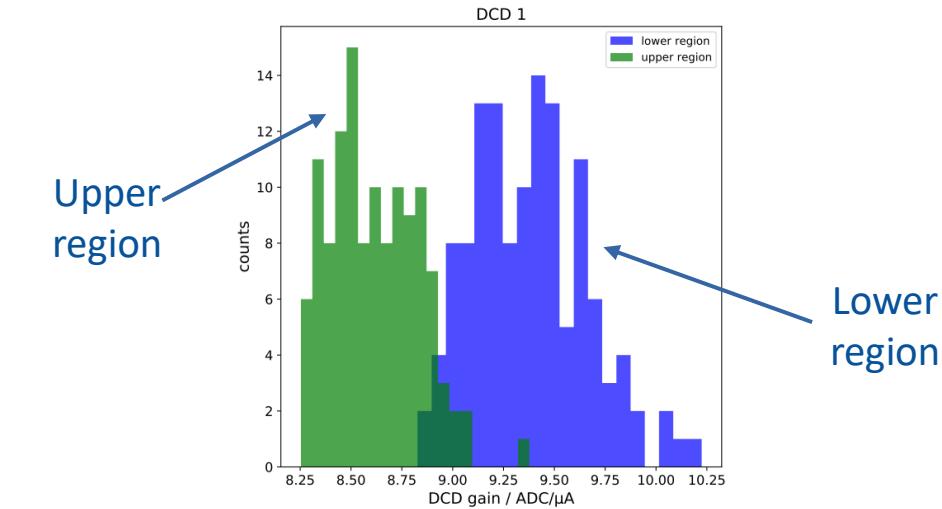
	W56_OF1	W56_OF1	W57_OB1	W57_OF2	W57_IB	W60_OF1
DCD gain ADU/ μ A	9.51	9.74	9.40	9.66	9.93	9.20

W60_OF1



DCD GAIN PER CHANNEL

- Deviations within upper and lower half DCD
 - Relative difference of around 6%
 - Internal voltage drop?



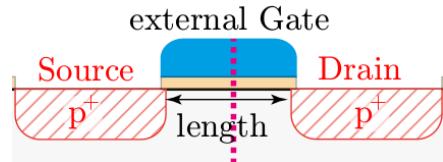
CHARACTERIZATION ON PIXEL LEVEL

Fundamental DEPFET pixel properties:

- **Transconductance g_m :** amplification of FET $g_m = \frac{\partial I_D}{\partial V_G}$
- **Charge amplification g_q :** amplification of pixel $g_q = \frac{\partial I_D}{\partial Q_{sig}}$
 - Rough expectation: $g_q \approx 400 - 600 \text{ pA}/e^-$
- Investigation on pixel level

TRANSCONDUCTANCE G_M

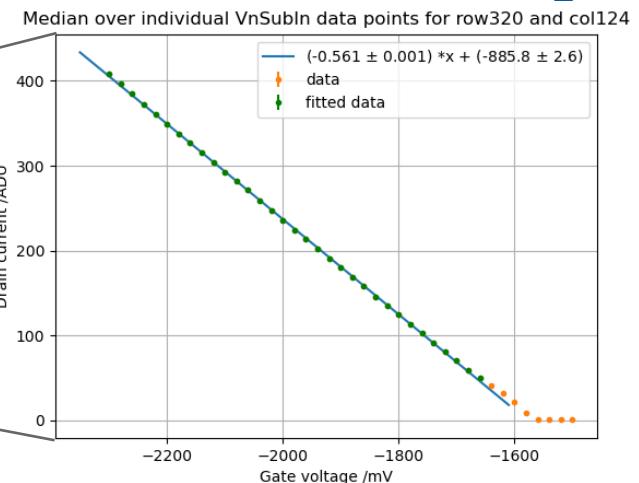
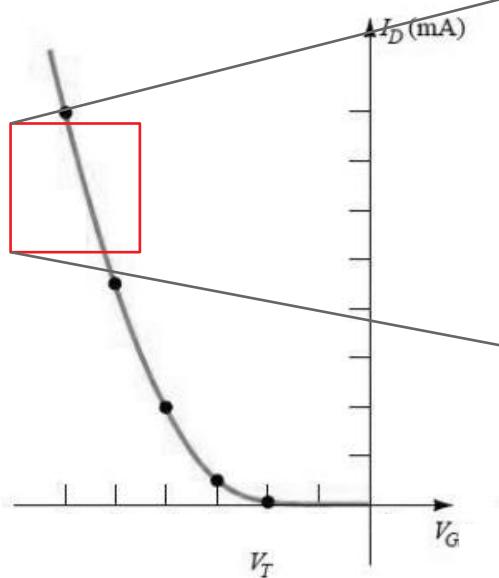
W60_OF1



$$g_m = \frac{\partial I_D}{\partial V_G}$$

I_D : measured current

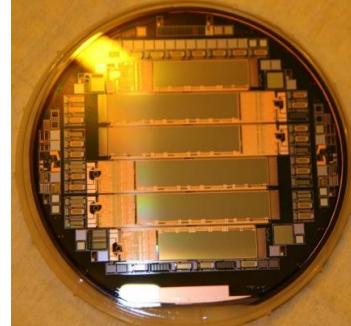
V_G : gate voltage



$$g_m = \frac{slope}{A_{DCD}} = -62.9 \frac{\mu A}{V}$$

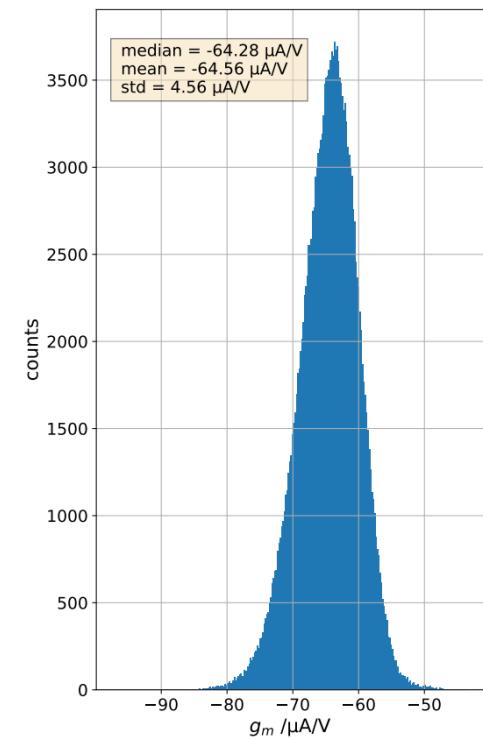
A_{DCD} : DCD Gain

RESULTS OF G_M MEASUREMENT



Ladislav Andricek, MPG Halbleiterlabor

W60_OF1

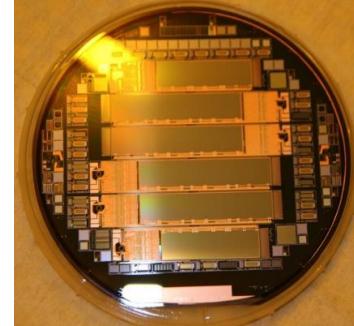


Wafer number

Location in detector

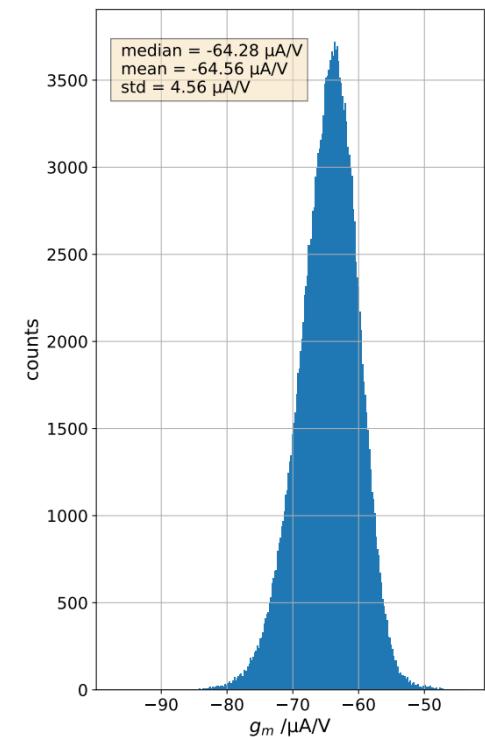
		W56_OF1	W57_OF1	W57_OF2	W57_IB	W60_OF1	W67_IB
$g_m / \frac{\mu\text{A}}{\text{V}}$	-72.8	-73.4	-61.7	-65.9	-65.6	-64.3	-46.0

RESULTS OF G_M MEASUREMENT



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W60_OF1



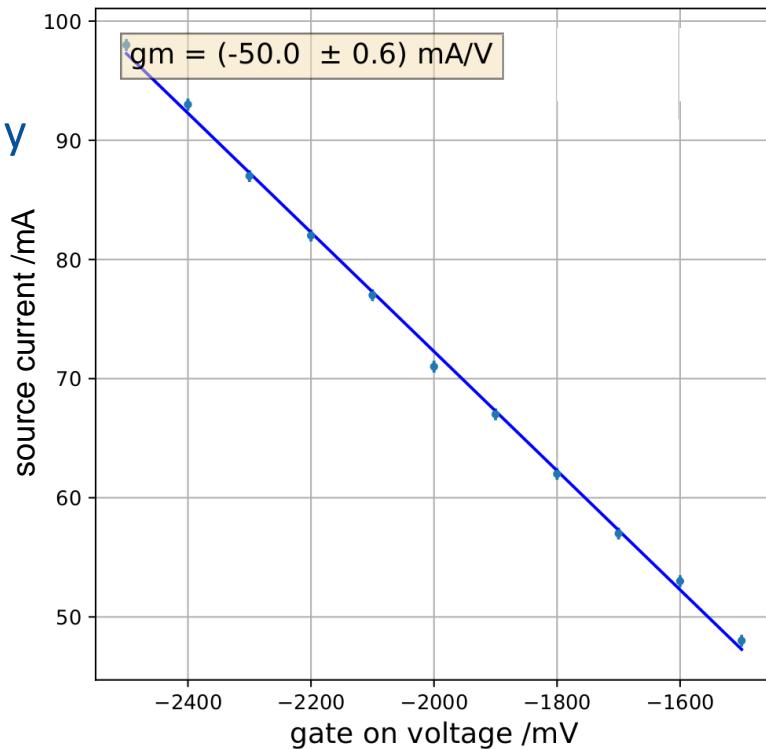
	W56_OB1	W56_OF1	W57_OB1	W57_OF2	W57_IB	W60_OF1	W67_IB
$g_m / \frac{\mu\text{A}}{\text{V}}$	-72.8	-73.4	-61.7	-65.9	-65.6	-64.3	-46.0

→ Dependence between wafer and mean g_m observed

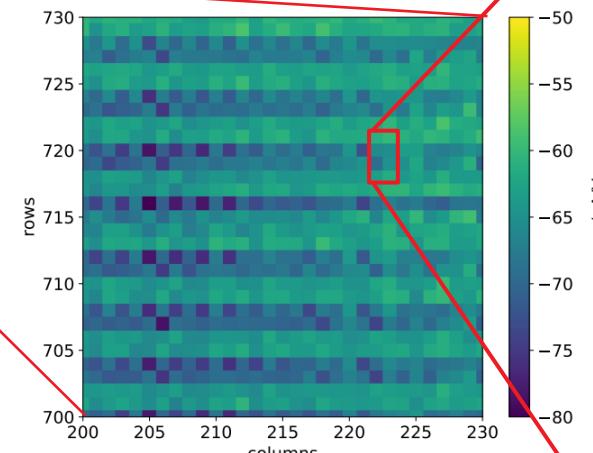
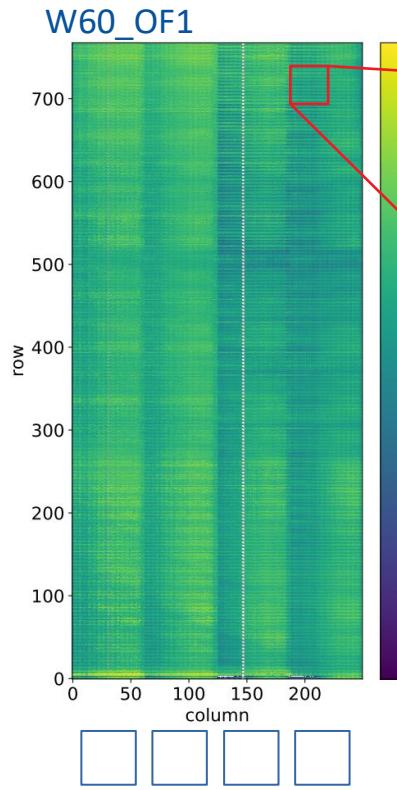
CROSS-CHECK FOR G_M MEASUREMENT

W67_IB

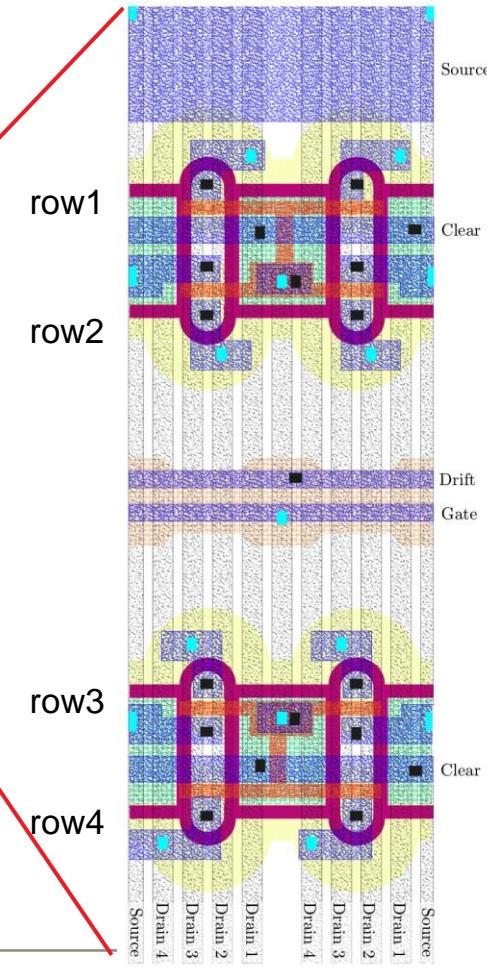
- Read drain current directly from power supply
- g_m measured over all drain lines
(not per pixel!)
- Previous method: $-46.45 \frac{\mu\text{A}}{\text{V}}$ with std. of
 $6.6 \frac{\mu\text{A}}{\text{V}}$ over all pixels
- Cross-check value: $(-50.0 \pm 0.6) \frac{\mu\text{A}}{\text{V}}$



G_M PIXEL STRUCTURES



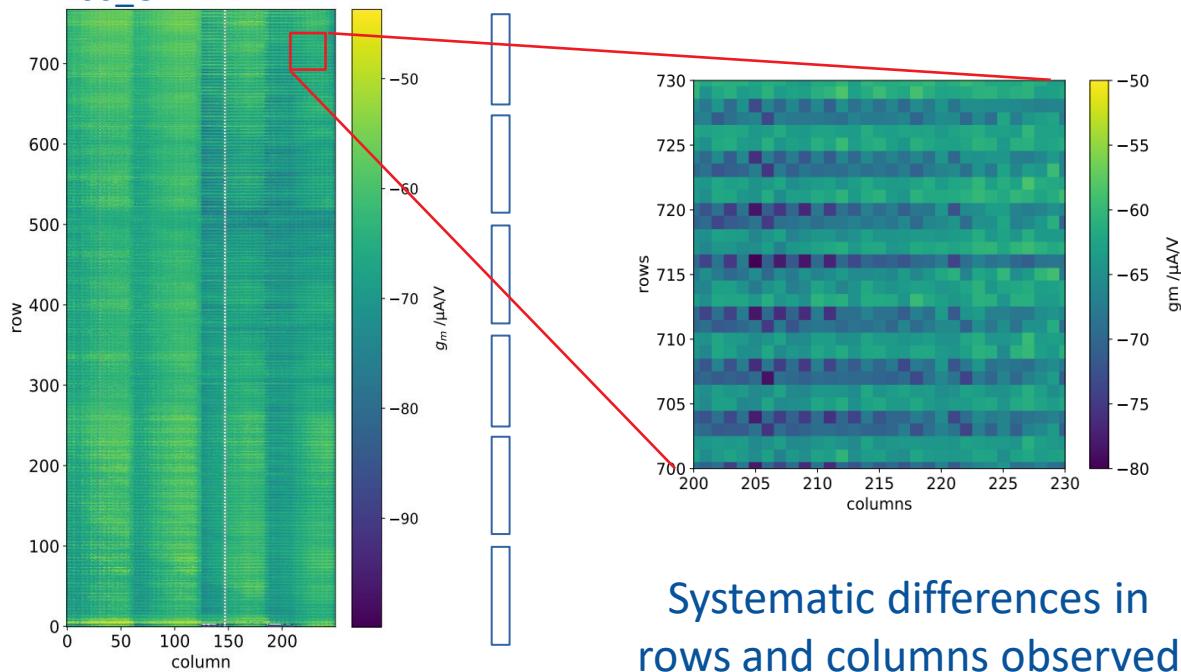
Systematic differences in
rows and columns observed



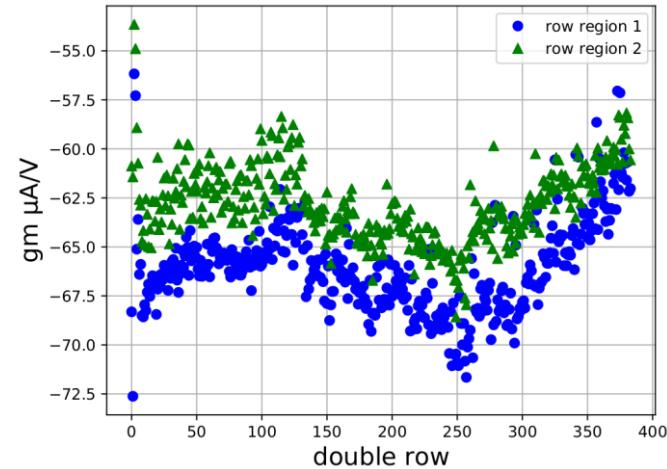
Felix Müller (2017):
Characterization and optimization
of the prototype DEPFET
modules for the
Belle II Pixel
Vertex Detector

PROJECTION TRANSCONDUCTANCE G_M : ROWS

W60_OF1

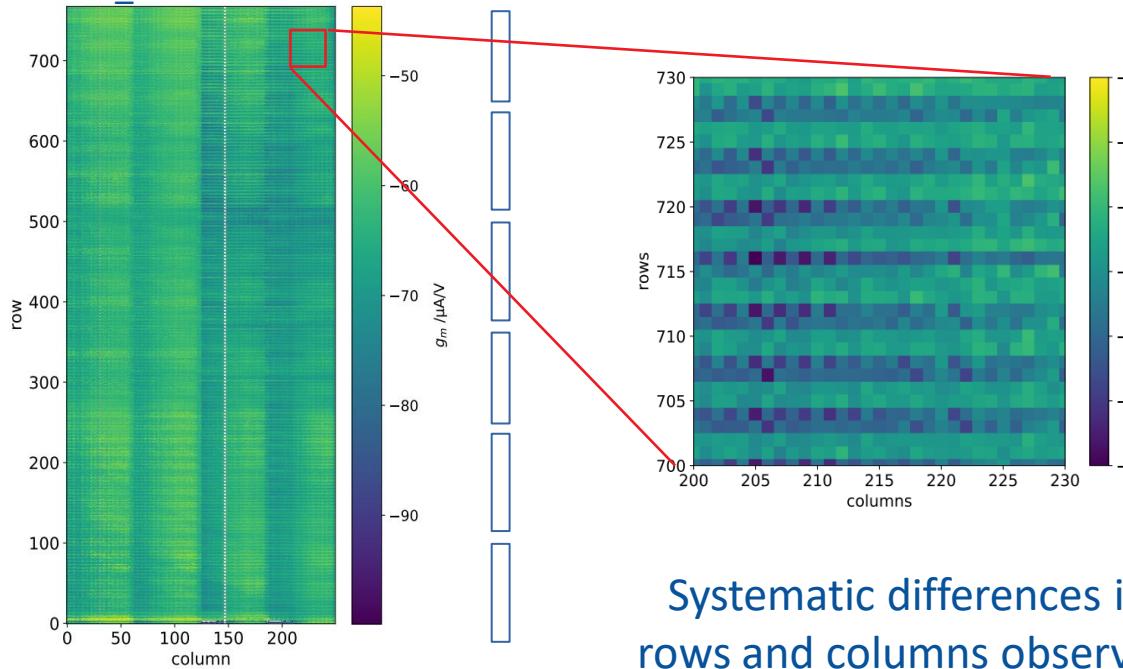


Systematic differences in
rows and columns observed



PROJECTION TRANSCONDUCTANCE G_M : COLUMNS

W60_OF1



Systematic differences in
rows and columns observed

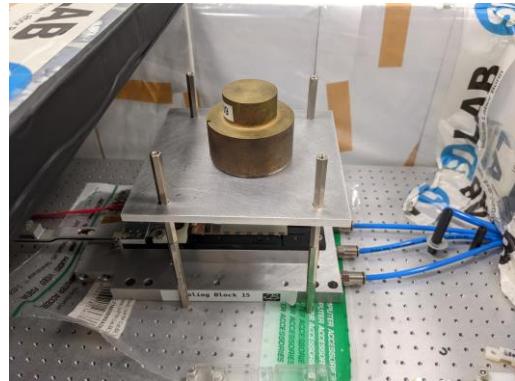
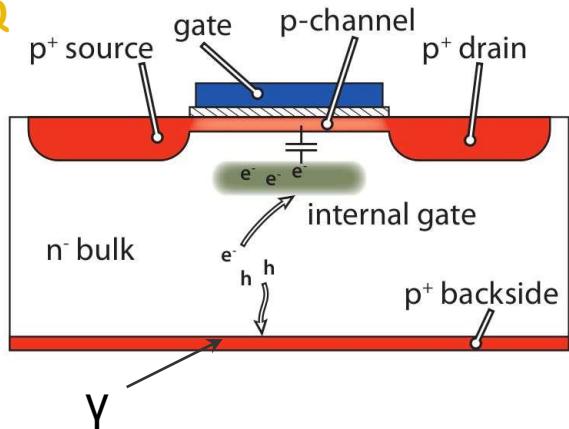


CHARGE AMPLIFICATION G_Q

$$g_q = \frac{\partial I_D}{\partial Q_{sig}}$$

I_D : measured current
 Q_{sig} : signal charge

- Signal generated with radioactive ^{109}Cd photon source (1850 MBq)
- 6300 electron-hole pairs in silicon



SINGLE PHOTON SPECTRUM

$$g_q = \frac{\mu}{A_{DCD}} \Big/ \frac{E_{K_\alpha}}{E_{eh}} = 743.8 \text{ pA/e}^-$$

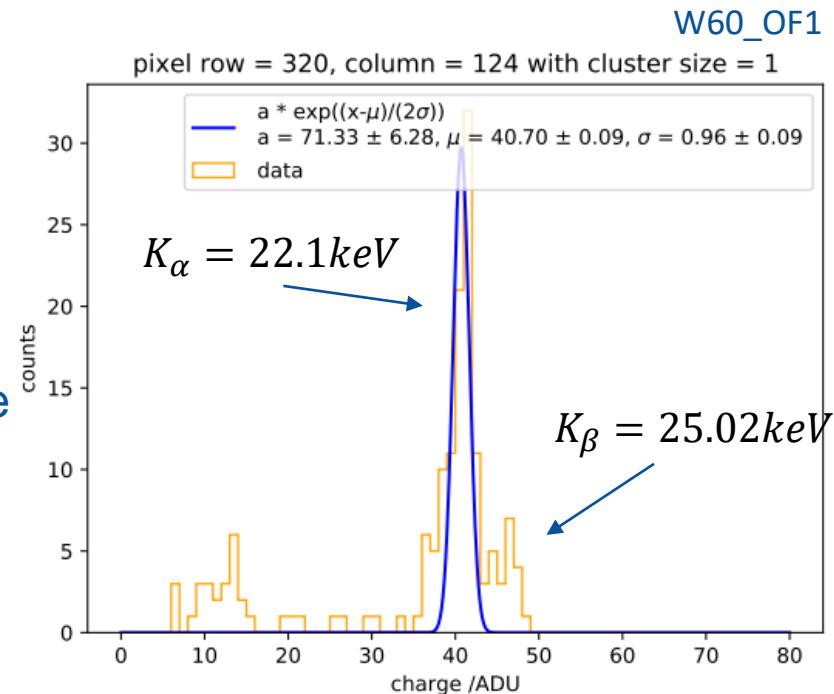
$$E_{eh} = 3.65 \text{ eV/e}^-$$

average energy to create electron-hole pair

E_{K_α} : energy ^{109}Cd K_α

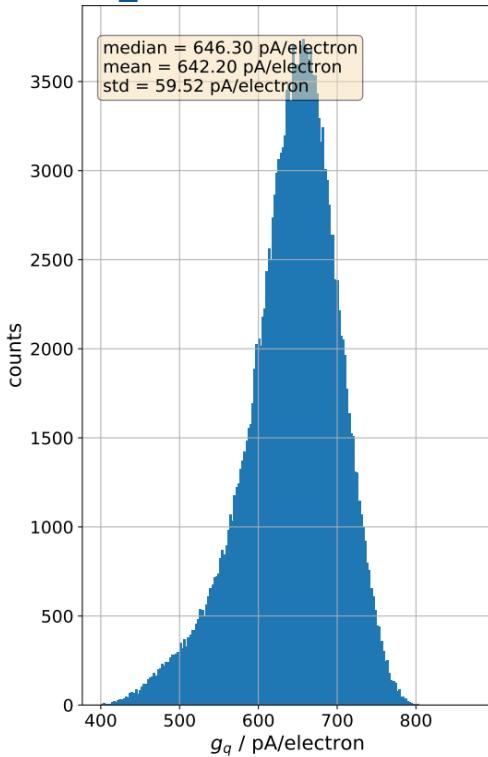
μ : measured K_α peak

A_{DCD} : DCD Gain



RESULTS OF G_Q MEASUREMENT

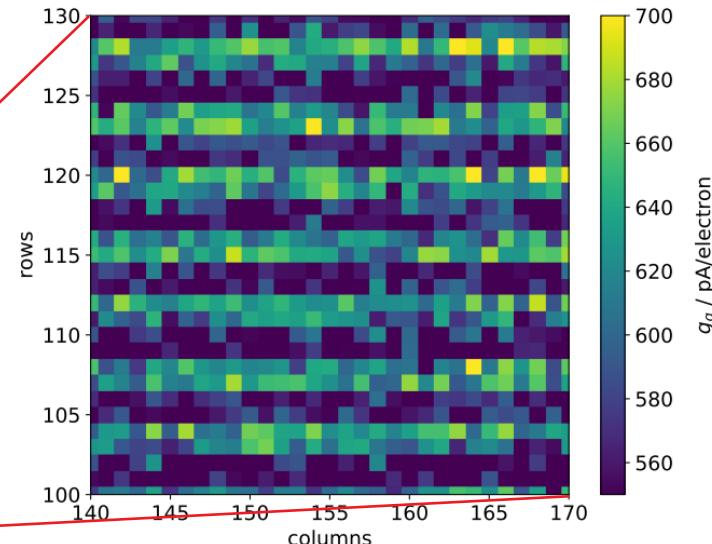
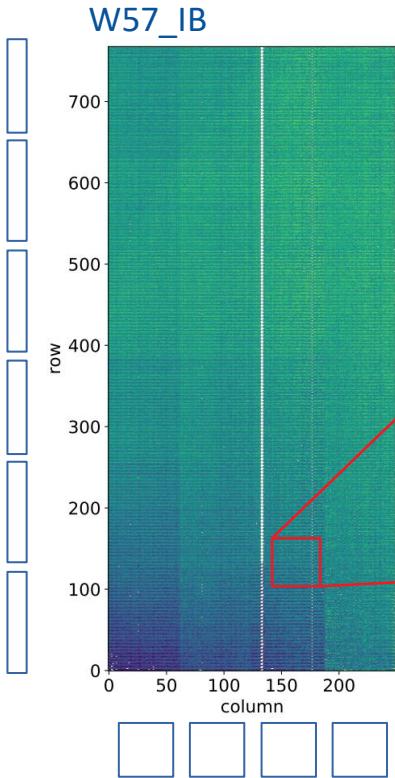
W57_IB



	W60_OF1	W57_IB	W67_IB
$g_q / pA/e^-$	743.91	648.55	517.40

- Assumed: $g_q \approx 400 - 600 \text{ pA}/e^-$
- All measured with gate-on = 2.1V
- Different source current

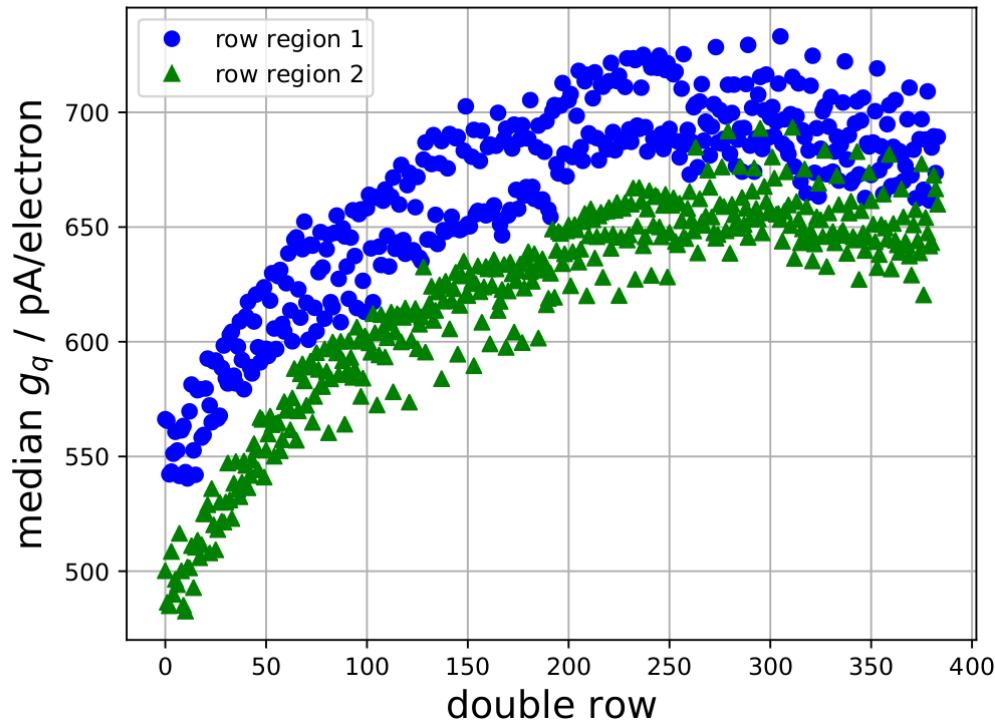
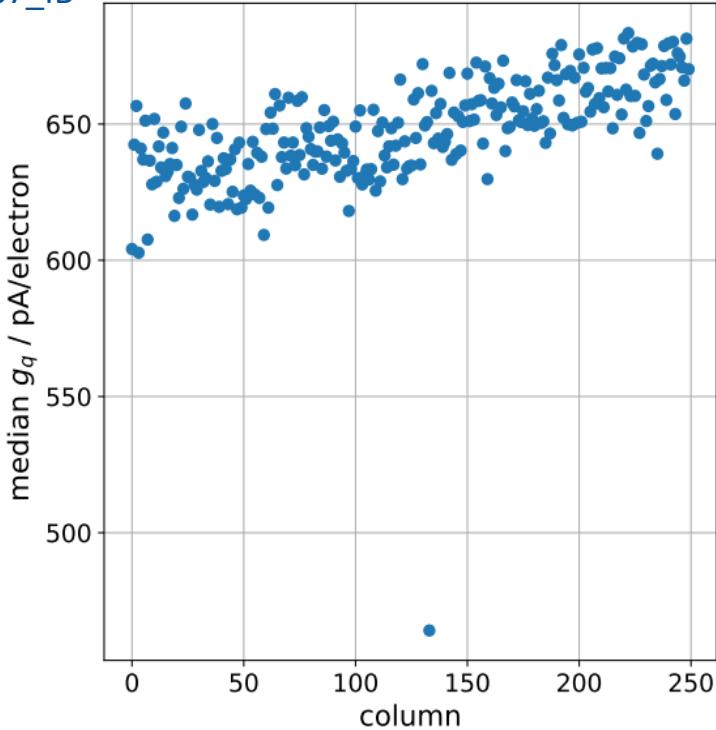
G_Q PIXEL STRUCTURES



– Double row effect also visible!

PROJECTION OF CHARGE AMPLIFICATION G_Q

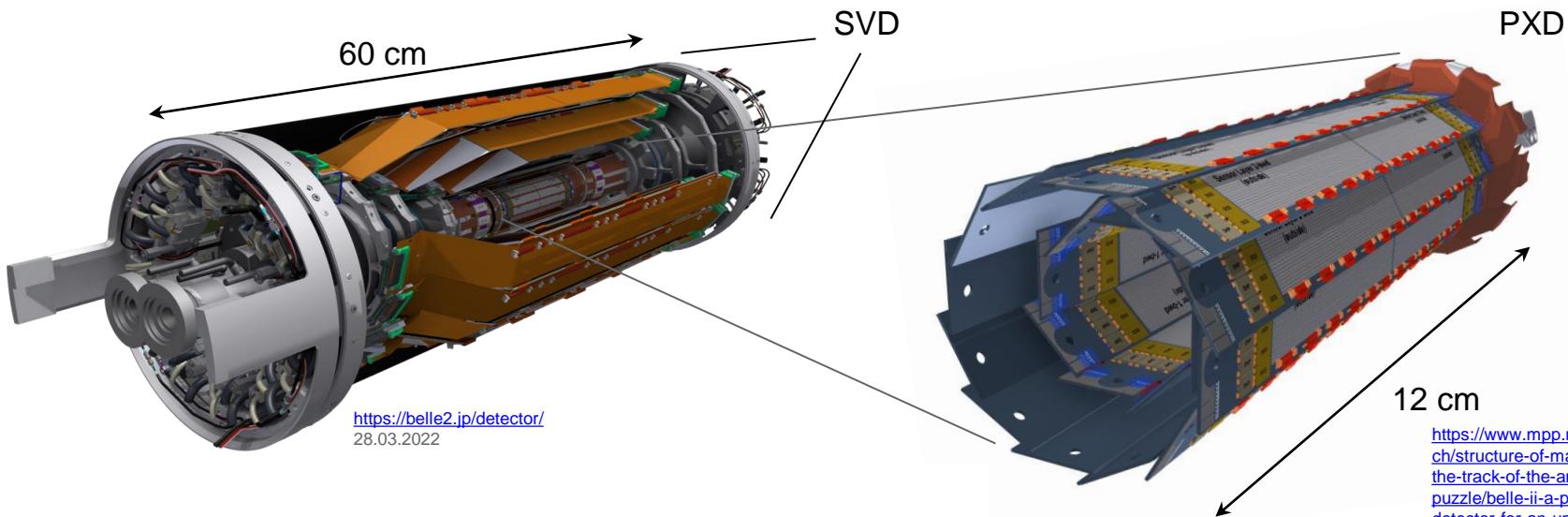
W57_IB



CONCLUSION

- Biasing Voltage Studies
 - Potential couplings between Implants and FET
- Detailed channel by channel /pixel by pixel characterization
 - Deviations between modules
 - More statistics needed for g_q ! Observed wafer dependent variations in g_m
 - Recurring pattern inside sensitive area → Several patterns under investigation
- Outlook: Different structures when irradiating modules?
 - All plots for all tested modules can be found in Larissa's thesis

VERTEX DETECTOR



- 4 layers of double sided silicon strips (SVD)
 - $R = 3.9 \text{ cm}, 8.0 \text{ cm}, 10.4 \text{ cm}, 13.5 \text{ cm}$
 - Area $\sim 1 \text{ m}^2$

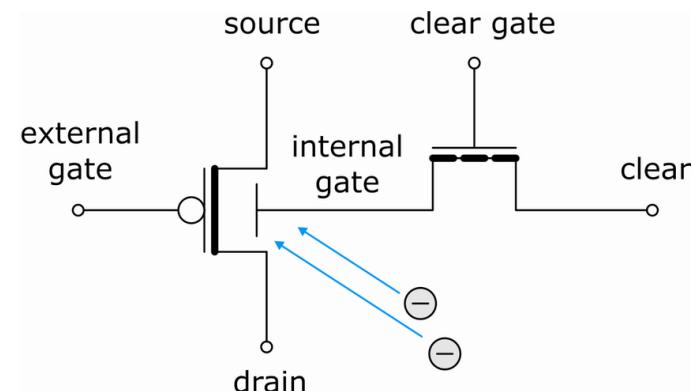
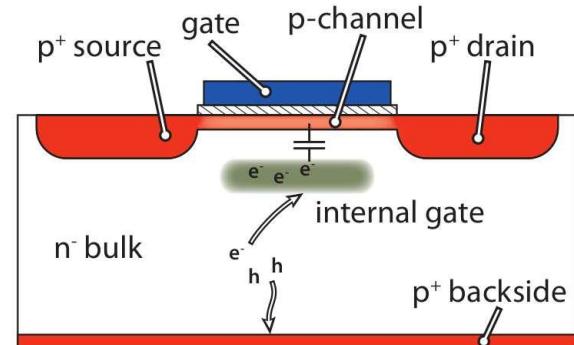
- 2 layers DEPFET pixel detector (PXD)
 - $R = 1.4 \text{ cm}, 2.2 \text{ cm}$
 - Area $\sim 0.03 \text{ m}^2$

<https://www.mpp.mpg.de/en/research/structure-of-matter/belle-ii-on-the-track-of-the-antimatter-puzzle/belle-ii-a-pixel-vertex-detector-for-an-updated-accelerator>

THE DEPFET PIXEL

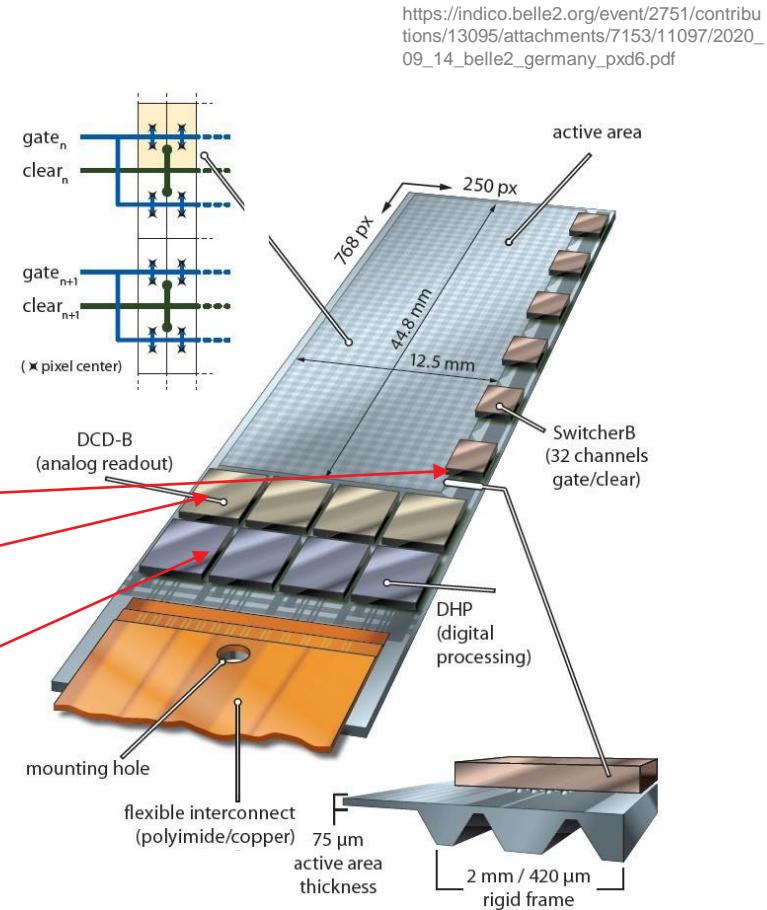
- Field Effect Transistor (FET): source, gate, drain
- Depleted silicon bulk
- Fast charge collection in internal gate (~ns)
 - Modulates drain current I_D
- Additional FET for clear mechanism
 - Internal gate cleared periodically
 - Clear-on voltage applied at clear contact
- Pedestals: drain current without charge inside internal gate

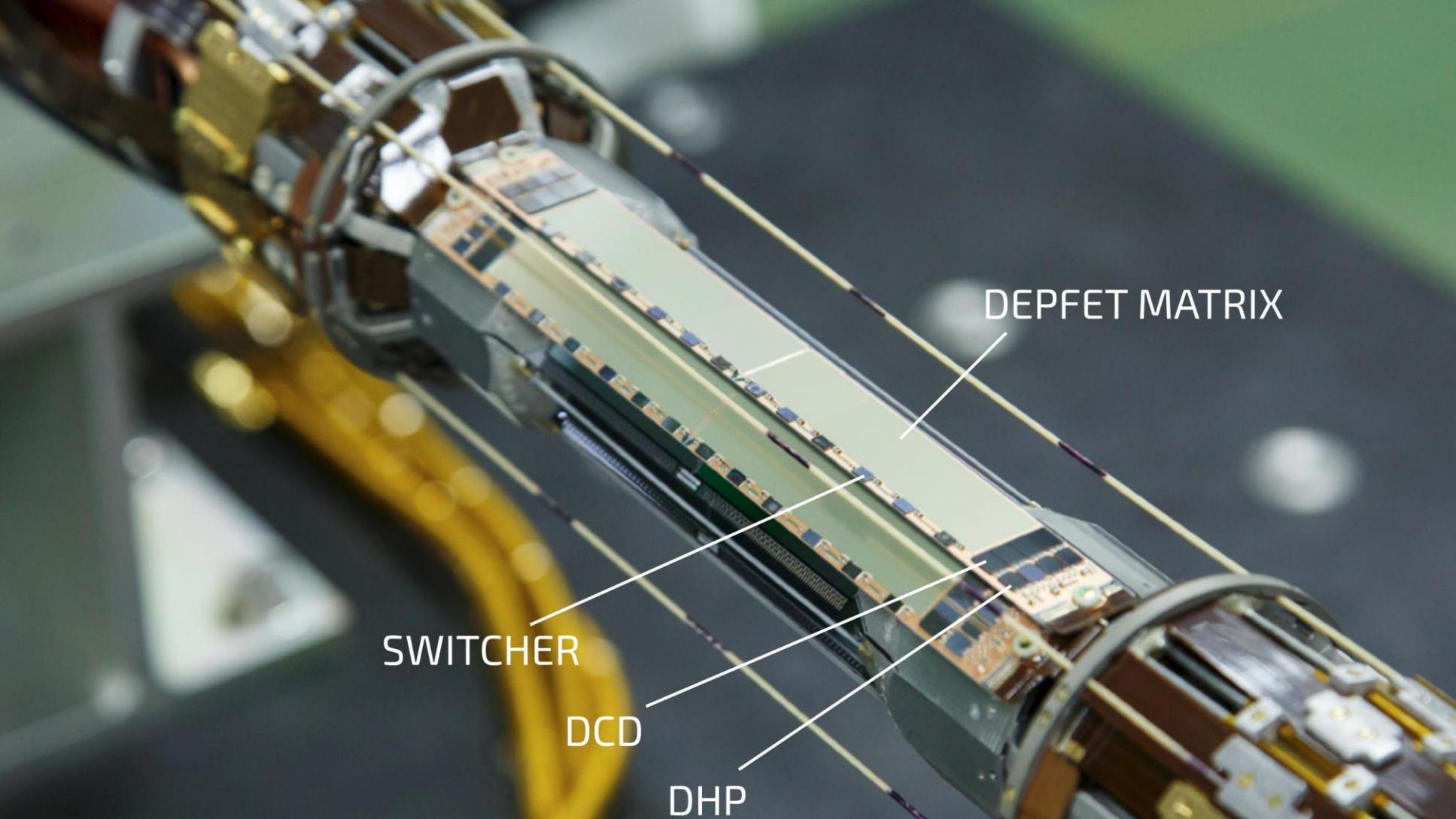
$$I_{sig} = I_D - I_{ped}$$



THE PXD MODULE

- Thickness of active area: 75 µm
- Rolling shutter readout: row wise
 - Drain current read with ~20 µs integration time
 - Controlled by gate and clear voltage
- **Switcher:**
 - Control gate and clear lines
- **Drain Current Digitizer (DCD):**
 - 256 Analog to Digital Converters (ADCs)
 - Digitizes drain current
- **Data Handling Processor (DHP):**
 - Processes data further





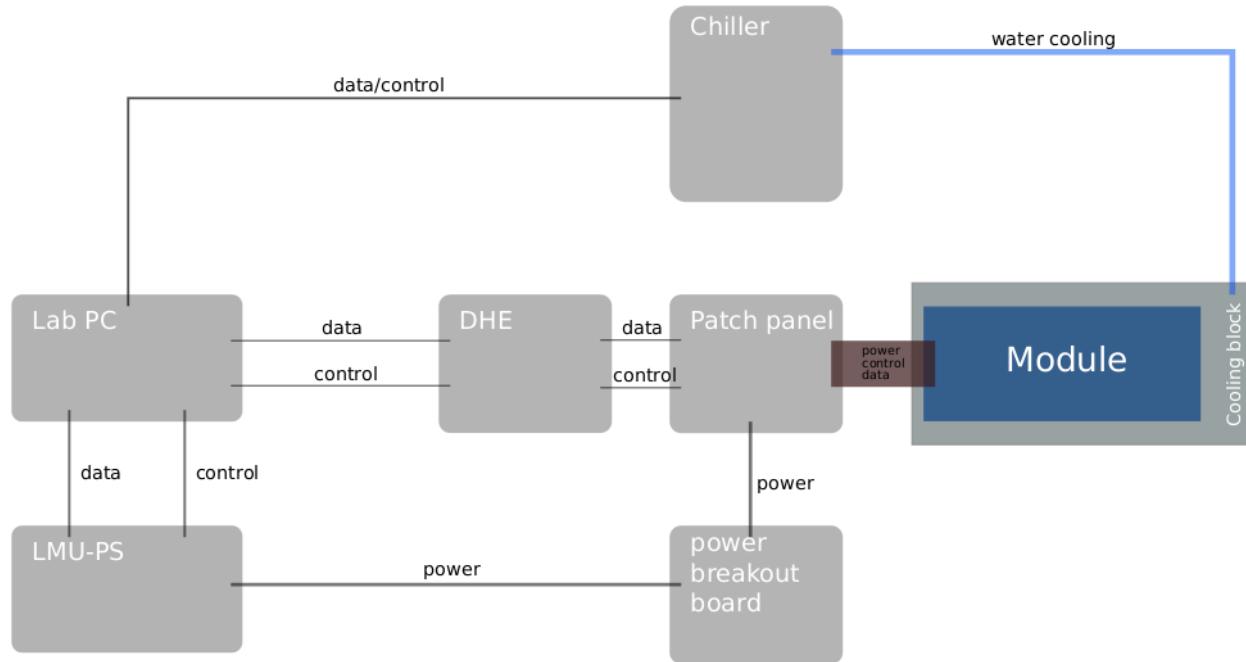
DEPFET MATRIX

SWITCHER

DCD

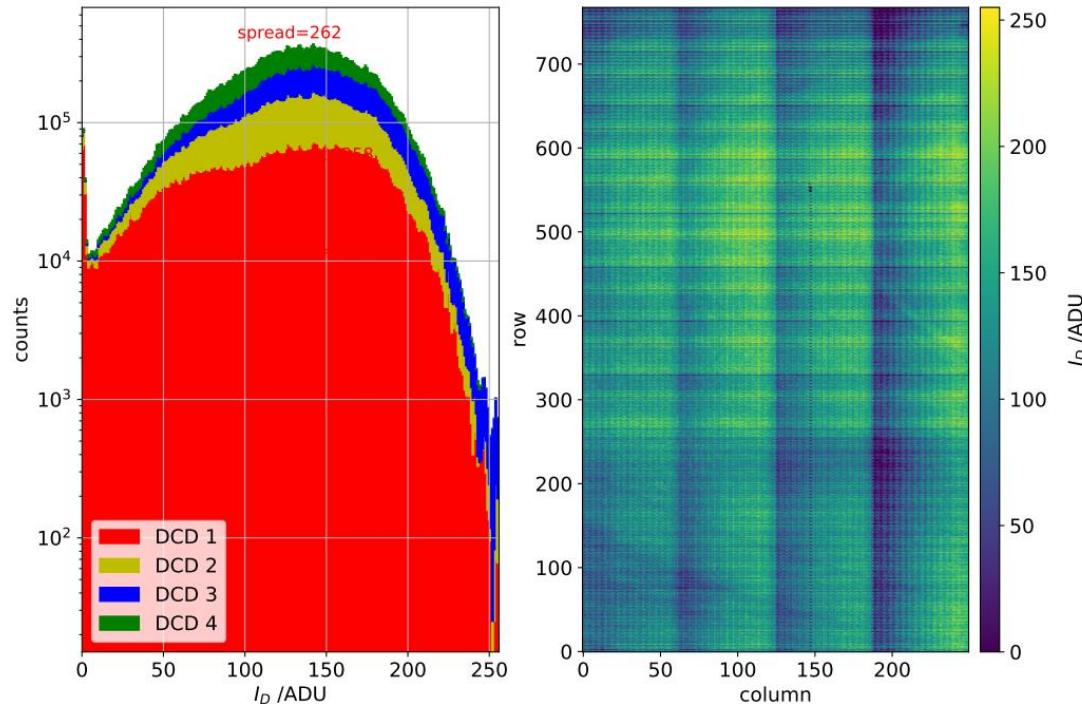
DHP

MODULE TESTING SETUP



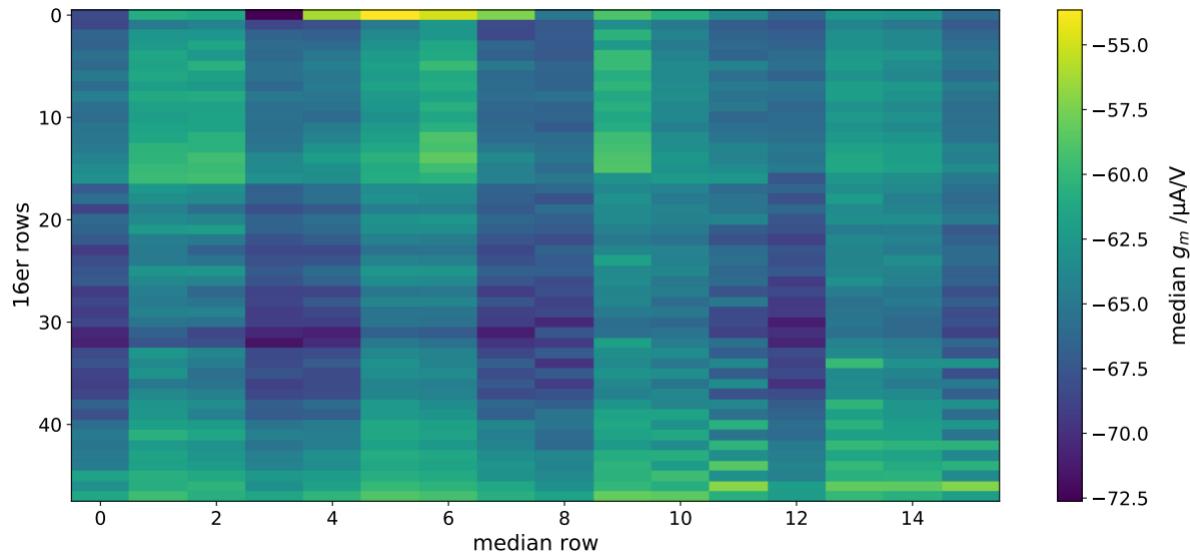
PEDESTALS

- Spread due to:
 - Process variations
 - DCD gain influence
 - g_m and threshold
- Pedestals need to be uploaded frequently:
 - Temperature
 - Radiation



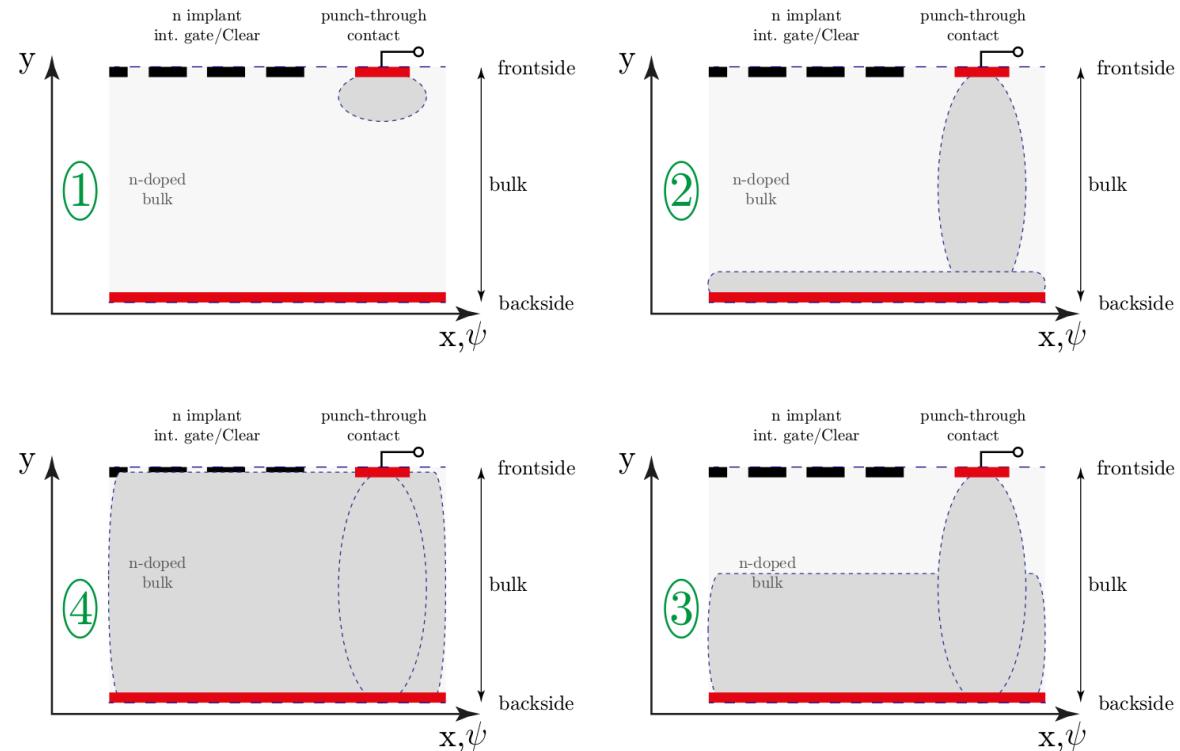
16ER ROW PATTERN

- Differences in pattern for larger/smaller pixel
 - Production of implants
 - Lithography masks overlapping



DEPLETION DEPFET PIXEL

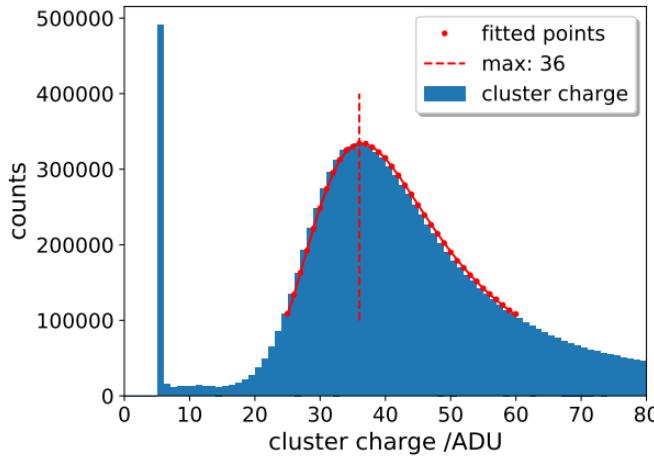
- 1) high voltage (hV) applied to punch-through contact
- 2) $hV \sim -35$ V depletion zone spreads to the backside
- 3) Bulk starts to get depleted
- 4) Bulk fully depleted



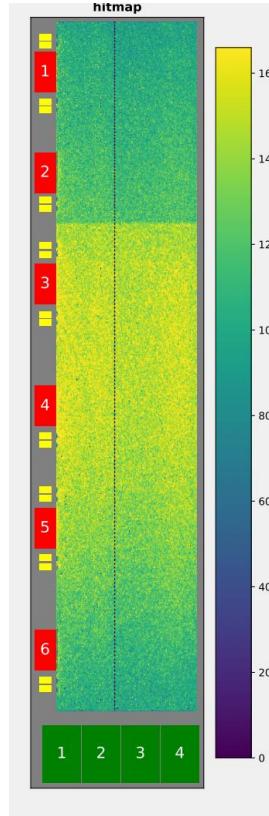
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MATRIX BIASING

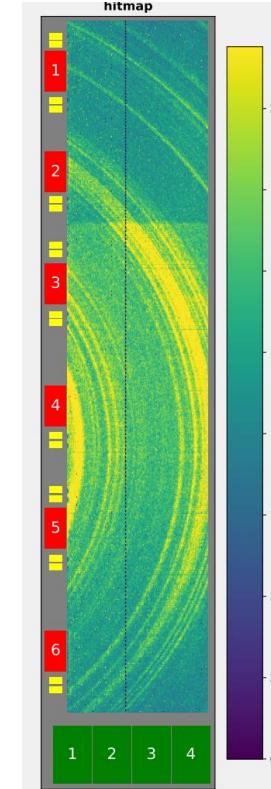
- Optimal bulk depletion
 - Homogeneous pixel response
 - Highest charge collection efficiency



hv: - 51V
 drift: - 5V
 clear: 3V



good setting



bad setting

^{90}Sr (33MBq)